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Article

Investigation of WO_3 Electrodeposition Leading to Nanostructured Thin Films

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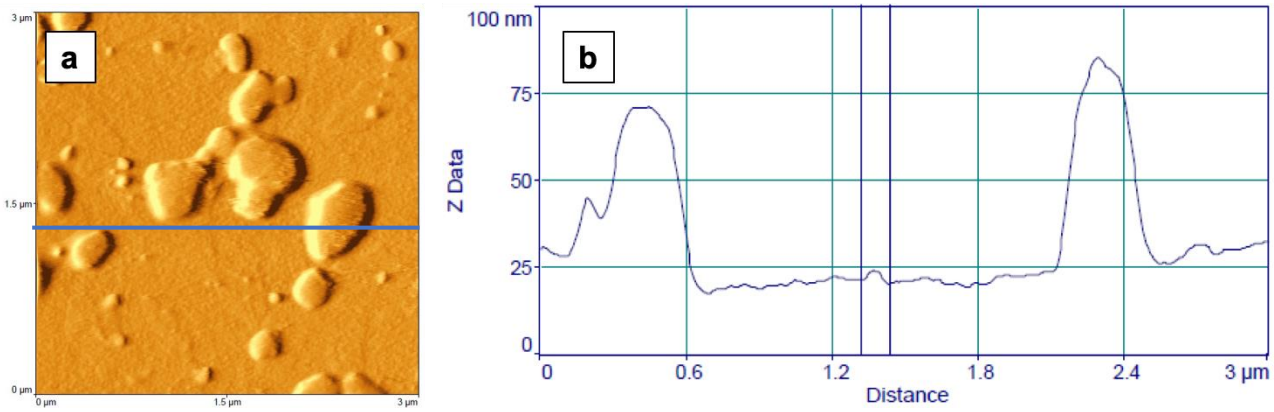

Figure S1. (**a**) AFM image of the sample deposited by applying V_d = 0.45 V for 6 s. The blue line identifies the region in which the line spectrum showed in (**b**) is obtained.

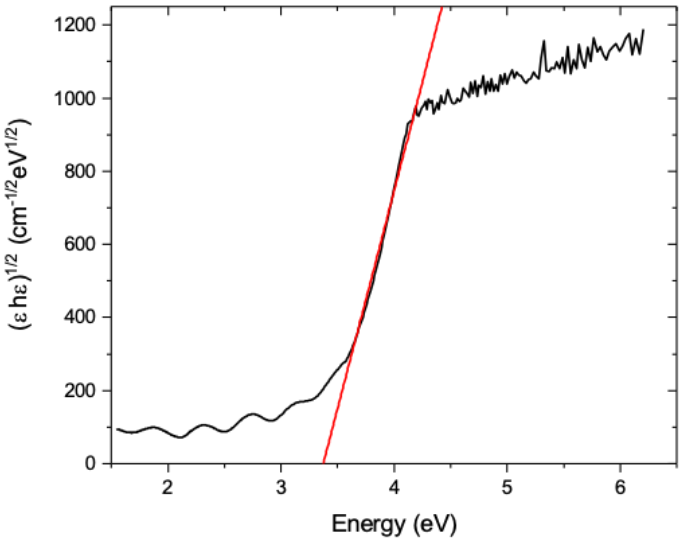

Figure S2. Tauc plot of sample deposited at V_d = 0.45 V for 3 min. The red line is the linear fit.

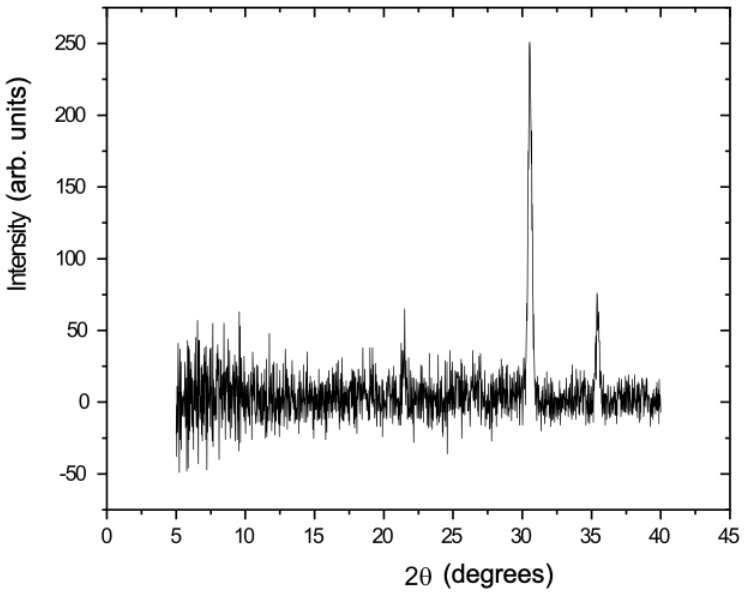

Figure S3. XRD pattern of the sample deposited by applying V_d = 0.45 V for 3 min. The peaks are related to the ITO presence in the substrate.

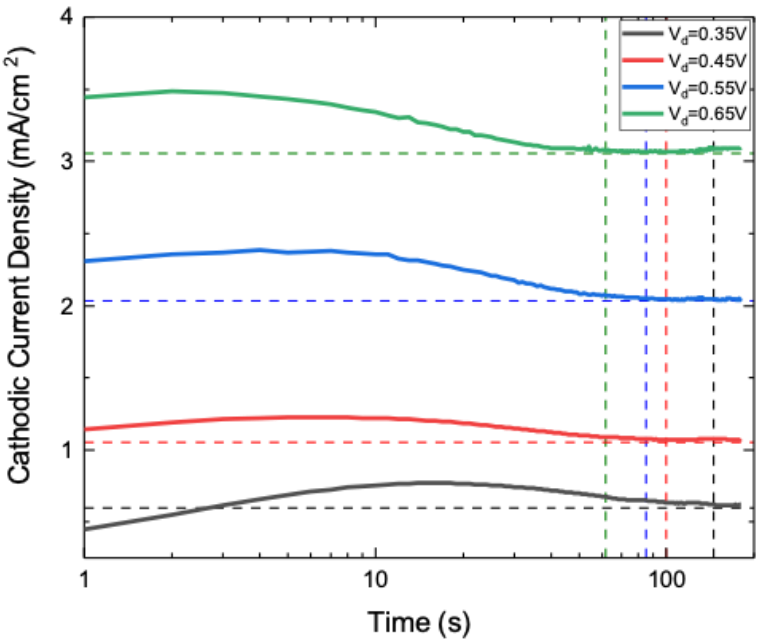

Figure S4. Current transients recorded during the samples electrodeposition by applying different V_d for 3 min. The dotted lines allow to individuate the different t_s for the different V_d values.

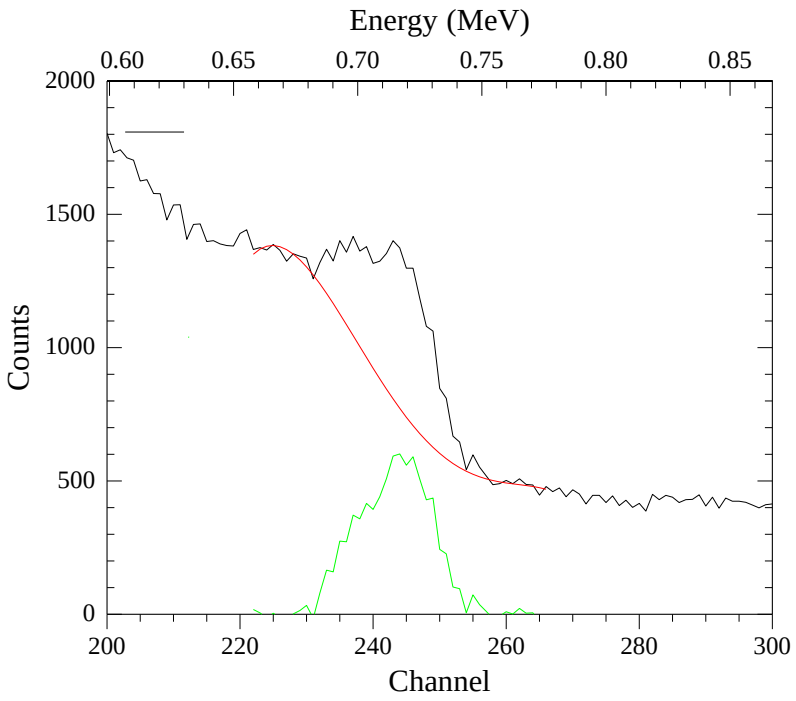

Figure S5. RBS spectrum, of the sample deposited by using V_d = 0.45 V for 1 min, acquired in glancing configuration. The red line is the line of the background, which was subtracted in order to individuate the peak related to the O content (green line).